

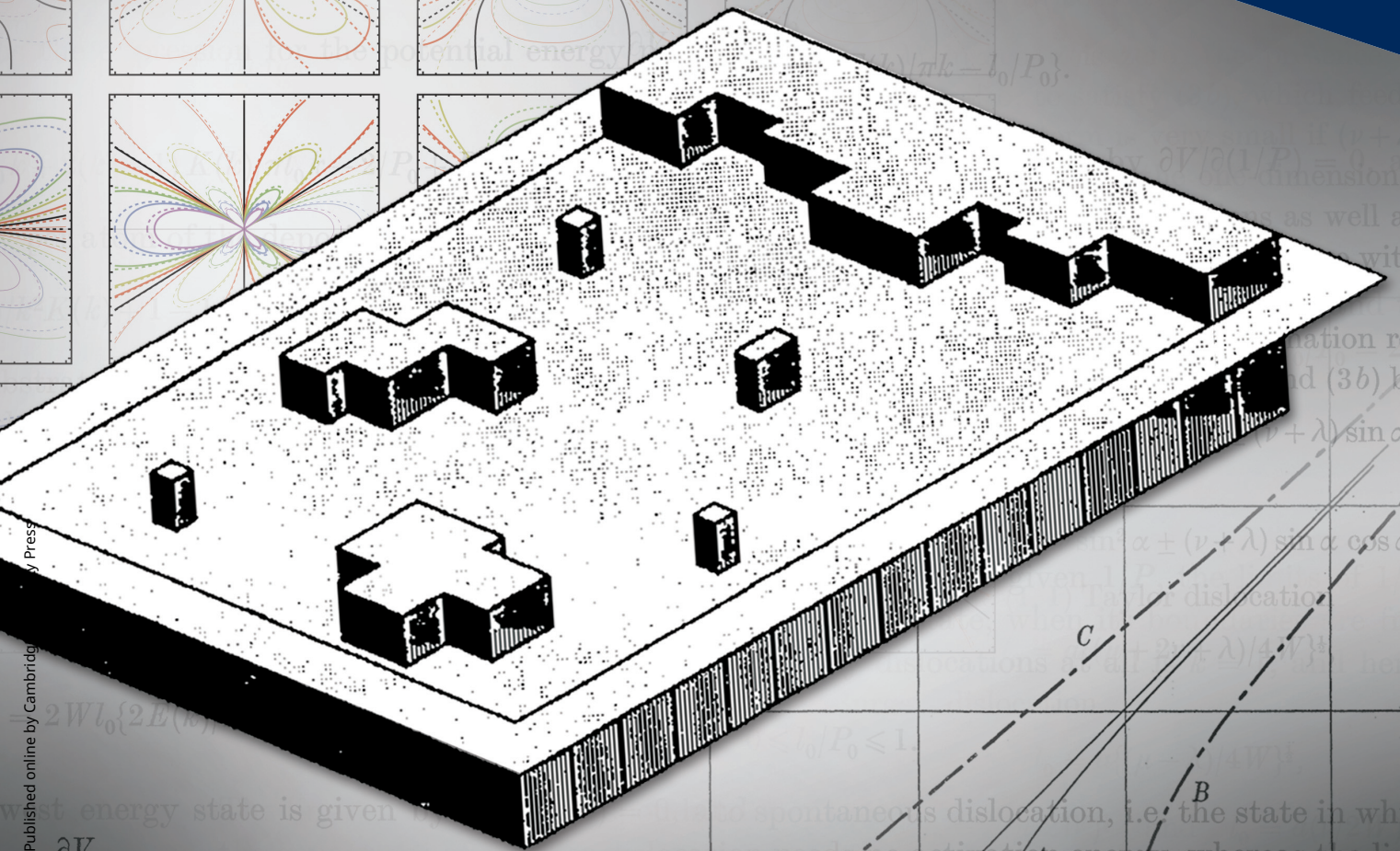


Journal of  
MATERIALS RESEARCH

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FOCUS ISSUE

Jan van der Merwe:  
Epitaxy and the Computer Age



$$\frac{\partial V}{\partial(1/P)} = 2Wl_0\{2E(k)/\pi k - l_0/P_0\}.$$

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